

Supporting Information

Dip-Pen Nanolithography of High Melting- Temperature Molecules

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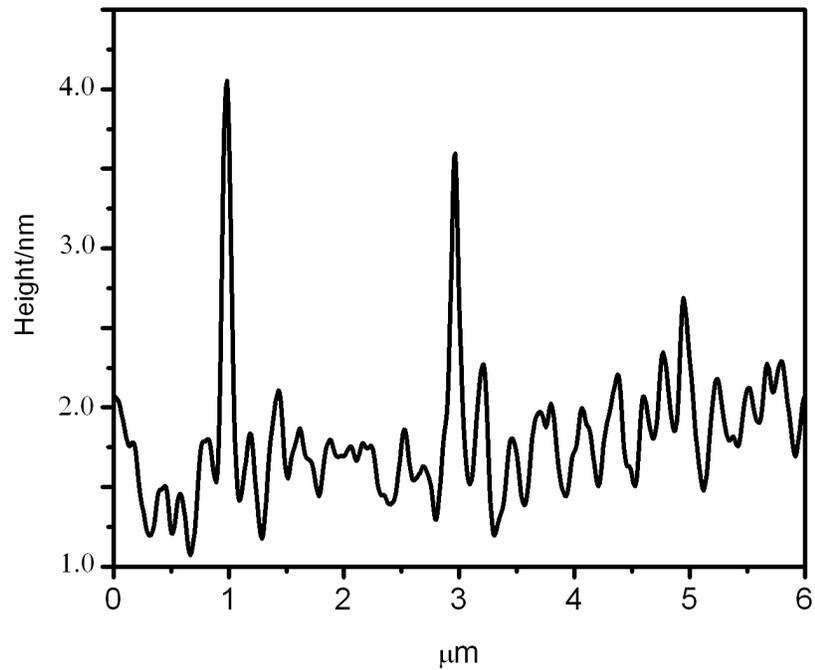


Figure S1. Height profile of OPA line arrays generated by DPN at writing speeds of 0.04, 0.16, and 0.64 $\mu\text{m}/\text{sec}$ (from left to right). The height profile was obtained from the topography AFM image shown in Figure 1B.

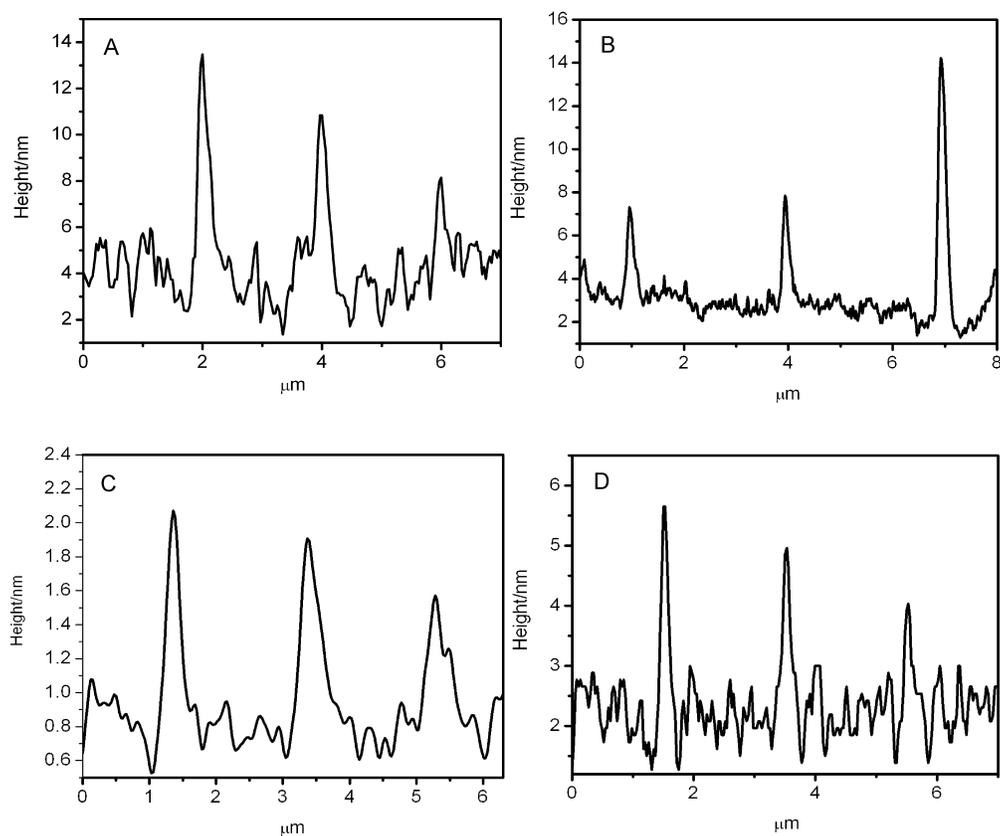


Figure S2. Height profiles of DPN line arrays of (A) 2MBT generated at writing speeds of: 0.1, 0.2, and 0.3 $\mu\text{m}/\text{sec}$ (from left to right); (B) Purpald generated at writing speeds of: 0.08, 0.04, and 0.02 $\mu\text{m}/\text{sec}$ (from left to right); (C) 4MP generated at writing speeds of: 0.1, 0.2, and 0.4 $\mu\text{m}/\text{sec}$ (from left to right), and (D) 2MI generated at writing speeds of: 0.05, 0.1, and 0.2 $\mu\text{m}/\text{sec}$ (from left to right). The humidity was $85 \pm 5\%$, and the temperature was maintained between 25 and 29 $^{\circ}\text{C}$. The height profiles were obtained from the topography AFM images shown in Figure 4.